20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

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| Session Title: | [MD2] EUV Resist Ⅰ |
| Session Date: | November 14 (Mon.), 2022 |
| Session Time: | 15:00-17:00 |
| Session Room: | Room D (Sidney Room, 2F) |
| Session Chair: | Prof. Jin-Kyun Lee (Inha Univ., Korea) |

**[MD2-1] [Invited]** 15:00-15:30

Defect-Free EUV Patterning Using a Dry Deposited and Dry Developed EUV Photoresist System

Rich Wise (Lam Research, USA)

**[MD2-2] [Invited]** 15:30-16:00

Controlling EUV Resist Stochastics

Greg Denbeaux (SUNY Polytechnic Inst., USA)

**[MD2-3]** 16:00-16:20

Non-Chemically Amplified Extreme UV Resists based on the Unique Decomposition Behavior of Fluorinated Materials

Yejin Ku (Inha Univ., Korea), Sangsul Lee (POSTECH, Korea), Byung Jun Jung (Univ. of Seoul, Korea), and Jin-Kyun Lee (Inha Univ., Korea)

**[MD2-4]** 16:20-16:40

EUV CAR Resist Sensitivity Improvement

Jeongsik Kim, Jaehyun Kim, Myounghyun Hur, Minja Yoo, and Hyungkun Lee (Dongjin Semichem Co., Ltd., Korea)

**[MD2-5]** 16:40-17:00

EUV Photoresist for Ultra-Fine Nanopatterns

Seong-Ji Ha and Ji-Hyun Jang (UNIST, Korea)